Sozaraj Rasappa

List of Publications by Year in descending order

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29	628	623734	580821
papers	citations	14 h-index	25 g-index

29	29	29	882
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	A facile route to synthesis of S-doped TiO2 nanoparticles for photocatalytic activity. Journal of Molecular Catalysis A, 2015, 406, 51-57.	4.8	96
2	Plasma etch technologies for the development of ultra-small feature size transistor devices. Journal Physics D: Applied Physics, 2011, 44, 174012.	2.8	80
3	Swift Nanopattern Formation of PS-b-PMMA and PS-b-PDMS Block Copolymer Films Using a Microwave Assisted Technique. ACS Nano, 2013, 7, 6583-6596.	14.6	67
4	Orientation and Alignment Control of Microphase-Separated PS-b-PDMS Substrate Patterns via Polymer Brush Chemistry. ACS Applied Materials & Interfaces, 2013, 5, 88-97.	8.0	36
5	Self-assembly of polystyrene-block-poly(4-vinylpyridine) block copolymer on molecularly functionalized silicon substrates: fabrication of inorganic nanostructured etchmask for lithographic use. Journal of Materials Chemistry C, 2013, 1, 7941.	5.5	34
6	Study of the Kinetics and Mechanism of Rapid Self-Assembly in Block Copolymer Thin Films during Solvo-Microwave Annealing. Langmuir, 2014, 30, 10728-10739.	3.5	34
7	Fabrication of a sub-10 nm silicon nanowire based ethanol sensor using block copolymer lithography. Nanotechnology, 2013, 24, 065503.	2.6	30
8	Molecularly Functionalized Silicon Substrates for Orientation Control of the Microphase Separation of PS-b-PMMA and PS-b-PDMS Block Copolymer Systems. Langmuir, 2013, 29, 2809-2820.	3.5	30
9	High quality sub-10 nm graphene nanoribbons by on-chip PS-b-PDMS block copolymer lithography. RSC Advances, 2015, 5, 66711-66717.	3.6	22
10	High molecular weight block copolymer lithography for nanofabrication of hard mask and photonic nanostructures. Journal of Colloid and Interface Science, 2019, 534, 420-429.	9.4	22
11	Block copolymer lithography: Feature size control and extension by an over-etch technique. Thin Solid Films, 2012, 522, 318-323.	1.8	21
12	Soft Graphoepitaxy for Large Area Directed Selfâ€Assembly of Polystyreneâ€blockâ€Poly(dimethylsiloxane) Block Copolymer on Nanopatterned POSS Substrates Fabricated by Nanoimprint Lithography. Advanced Functional Materials, 2015, 25, 3425-3432.	14.9	20
13	Nanopatterning via Self-Assembly of a Lamellar-Forming Polystyrene-block-Poly(dimethylsiloxane) Diblock Copolymer on Topographical Substrates Fabricated by Nanoimprint Lithography. Nanomaterials, 2018, 8, 32.	4.1	19
14	Rapid, Brushless Self-assembly of a PS-b-PDMS Block Copolymer for Nanolithography. Colloids and Interface Science Communications, 2014, 2, 1-5.	4.1	17
15	Tuning PDMS Brush Chemistry by UVâ€“O₃ Exposure for PS-b-PDMS Microphase Separation and Directed Self-assembly. Langmuir, 2013, 29, 8959-8968.	3.5	13
16	Soft-graphoepitaxy using nanoimprinted polyhedral oligomeric silsesquioxane substrates for the directed self-assembly of PS-b-PDMS. European Polymer Journal, 2013, 49, 3512-3521.	5.4	12
17	The sensitivity of random polymer brush-lamellar polystyrene-b-polymethylmethacrylate block copolymer systems to process conditions. Journal of Colloid and Interface Science, 2013, 393, 192-202.	9.4	12
18	A Highly Efficient Sensor Platform Using Simply Manufactured Nanodot Patterned Substrates. Scientific Reports, 2015, 5, 13270.	3.3	12

#	Article	IF	Citations
19	Morphology evolution of PS- b -PDMS block copolymer and its hierarchical directed self-assembly on block copolymer templates. Microelectronic Engineering, 2018, 192, 1-7.	2.4	12
20	Directed self-assembly of a high-chi block copolymer for the fabrication of optical nanoresonators. Nanoscale, 2018, 10, 18306-18314.	5.6	10
21	Self-Assembled Nanofeatures in Complex Three-Dimensional Topographies via Nanoimprint and Block Copolymer Lithography Methods. ACS Omega, 2017, 2, 4417-4423.	3.5	5
22	Depth Profiling of PLGA Copolymer in a Novel Biomedical Bilayer Using Confocal Raman Spectroscopy. Langmuir, 2013, 29, 5905-5910.	3.5	4
23	Sub-15â€‰nm Silicon Lines Fabrication via PS-b-PDMS Block Copolymer Lithography. Journal of Nanomaterials, 2013, 2013, 1-7.	2.7	4
24	Nanoscale silicon substrate patterns from self-assembly of cylinder forming poly(styrene)-block-poly(dimethylsiloxane) block copolymer on silane functionalized surfaces. Nanotechnology, 2017, 28, 044001.	2.6	4
25	Graphoepitaxial Directed Selfâ€Assembly of Polystyreneâ€Blockâ€Polydimethylsiloxane Block Copolymer on Substrates Functionalized with Hexamethyldisilazane to Fabricate Nanoscale Silicon Patterns. Advanced Materials Interfaces, 2014, 1, 1300102.	3.7	3
26	Fabrication of <I>3</I>-<I>D</I> Nanodimensioned Electric Double Layer Capacitor Structures Using Block Copolymer Templates. Journal of Nanoscience and Nanotechnology, 2014, 14, 5221-5227.	0.9	3
27	Block Co-Polymers for Nanolithography: Rapid Microwave Annealing for Pattern Formation on Substrates. Polymers, 2015, 7, 592-609.	4.5	3
28	Fabrication of Germanium Nanowire Arrays by Block Copolymer Lithography. Science of Advanced Materials, 2013, 5, 782-787.	0.7	3
29	Block Copolymer Self-assembly on Ethylene Glycol (EG) Self-assembled Monolayer (SAM) for Nanofabrication. Materials Research Society Symposia Proceedings, 2012, 1450, 1.	0.1	0